

## WEND THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

: Confirmation No. 7255

Naoaki OGURE et al.

Docket No. 2001\_0686A

Serial No. 09/866,843

Group Art Unit 1763

Filed May 30, 2001

Examiner G.A. GOUDREAU

COATING, MODIFICATION AND ETCHING OF SUBSTRATE SURFACE WITH PARTICLE BEAM IRRADIATION OF THE SAME

TO GOOD SECONDER IS AUTHORIZED TO GOOD SEE ANY DEFICIENCY IN THE PEES FOR THIS PAPER TO DEPOSIT ACCOUNT NO. 23-0975

## RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

This is in response to the Restriction Requirement of November 3, 2004.

Applicants, by their undersigned representative, hereby elect the invention of Group I which corresponds to claims 21-23, 25-27, 29, 31-38, 40-43 and 54-58. This election is made with traverse for the following reasons.

The Restriction Requirement is respectfully traversed because it is believed that there would be no undue burden on the Examiner for continuing to examine both method and apparatus claims together. In this regard, the Examiner has examined and considered both method and apparatus claims as evidenced by the Office Actions of September 9, 2003 and April 7, 2004. Accordingly, because method and apparatus claims have already been examined and considered by the Examiner, it is respectfully submitted that there would be no undue burden on the Examiner to continue examining and considering both method and apparatus claims. Thus, it is respectfully submitted that all of currently pending claims 21-23, 25-27, 29, 31-38, 40-43 and 45-58 should be examined together.

Having made the required election, a full examination on the merits of the elected invention is hereby requested.

Respectfully submitted,

Naoaki OGURE et al.

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